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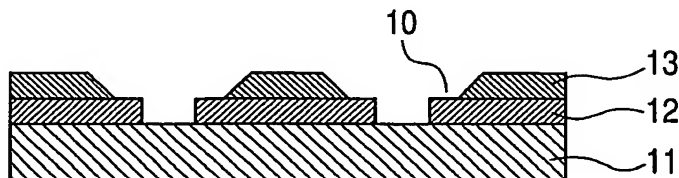
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(54) Title: METHOD FOR MANUFACTURING MINUTE STRUCTURE, METHOD FOR MANUFACTURING LIQUID DISCHARGE HEAD, AND LIQUID DISCHARGE HEAD



(57) Abstract: A method for manufacturing a minute structure comprises a step of forming a first ionizing radiation decomposing type positive type resist layer to be sensitized by an ionizing radiation of a first wavelength range, a step of forming a second ionizing radiation decomposing type positive type resist layer to be sensitized by an ionizing radiation of a second wavelength range on the first positive type photosensitive material layer, a step of form-

ing a desired pattern in the above-mentioned second positive type photosensitive material layer as the upper layer by decomposing reaction without decomposing reaction of the above-mentioned first positive type photosensitive material layer, development using a developing solution, and then, a step of forming a desired pattern in the above-mentioned first positive type photosensitive material layer as the lower layer by decomposing reaction of a predetermined area, and development, whereby a pattern of a convex shape is manufactured in the substrate by executing the above-mentioned steps.

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